

Title (en)
ELECTROPLATING BATH FOR ELECTROCHEMICAL DEPOSITION OF A CU-SN-ZN-PD ALLOY LAYER, METHOD FOR ELECTROCHEMICAL DEPOSITION OF SAID ALLOY LAYER, SUBSTRATE COMPRISING SAID ALLOY LAYER AND USES OF THE COATED SUBSTRATE

Title (de)
GALVANIKBAD ZUR ELEKTROCHEMISCHEN ABSCHIEDUNG EINER CU-SN-ZN-PD LEGIERUNGSSCHICHT, VERFAHREN ZUR ELEKTROCHEMISCHEN ABSCHIEDUNG DER LEGIERUNGSSCHICHT, SUBSTRAT MIT DER LEGIERUNGSSCHICHT UND VERWENDUNGEN DES BESCHICHTETEN SUBSTRATS

Title (fr)
BAIN GALVANIQUE POUR LE DÉPÔT ÉLECTROCHIMIQUE D'UNE COUCHE D'ALLIAGE CU-SN-ZN-PD, PROCÉDÉ DE DÉPÔT ÉLECTROCHIMIQUE DE CETTE COUCHE D'ALLIAGE, SUBSTRAT COMPRENANT CETTE COUCHE D'ALLIAGE ET UTILISATIONS DU SUBSTRAT REVÊTU

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Abstract (en)
The invention provides an electroplating bath for electrochemical deposition of a novel Cu-Sn-Zn-Pd alloy on a substrate. The novel alloy is characterized by exceptional corrosion resistance and the commonly used precious metal intermediate layer (e.g. a Pd-layer) between the substrate and the finishing layer is no longer necessary which allows a substantial reduction of the production costs of the plated substrates.

IPC 8 full level
C22C 9/02 (2006.01)

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Citation (applicant)
• EP 1930478 B1 20130619 - ENTHONE [US]
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Citation (search report)
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IT202000011203A1; IT201800004235A1; WO2021229481A1

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